IN THE CLAIMS

1-9. (canceled.)

10. (original) A method for producing a micro mirror unit comprising a frame and a mirror substrate, formed from a single substrate material, the mirror body having a mirror surface thereof formed on the mirror substrate being linked to the frame by means of hinges in such a manner that the mirror body is supported movably in relation to the frame, comprising:

a first step at which a material for the hinges are formed as layer on one main side of a substrate material for the frame and mirror substrate;

a second step at which a resist layer is formed on the other main side of the substrate material on which a mirror surface is formed; and

a third step at which the frame and mirror substrate are separated from each other by the dry etching using the resist layer as a mask.

11. (original) The method as set forth in Claim 10, wherein a material different in selection ratio to etching from the substrate material is used as a material for the hinge formed as a layer on the one main side of the substrate material at the first step; and

the material for the hinges are dry-etched as an etching stopper at the third step.

12. (original) The method as set forth in Claim 10, wherein a material for the hinge different in selection ratio to etching from the substrate material is formed as a layer on the one main side of the substrate material at the first step; and

a material different in selection ratio to etching from the substrate material is dry-etched as an etching stopper at the third step.

13. (currently amended) The method as set forth in Claim 10, wherein ~~the~~ a plasma CVD process is used to form the material for the hinge as a layer at the first step.

14. (original) The method as set forth in Claim 10, wherein the dry etching is effected by supplying SF_6 gas and CF_4 gas alternately as etching gases at the third step.